PHOTONICS SOCIETY at UCSB A STUDENT CHAPTER OF IPS, SPIE & OSA UCSB Student Lecturer Series

1:00 PM Friday, March 5th

Zoom Meeting – Meeting ID: 847 3105 9791 -- Password: 792878 Zoom Link



Caroline Reilly DenBaars Group Materials Dept, UCSB

10¹⁵ uncapped 12 nm 18 nm 23 nm 10¹⁰ Intensity 105 manterenter 10⁰ 14.5 15 15.5 16.5 17.5 18 18.5 16 ω-2θ (°)

InN Quantum Dots by MOCVD for Infrared Applications

The III-N system has proved successful for lightemitters in the high-energy visible and ultraviolet but has faced challenges in the lower-energy regime. The most common growth technique for devices. metalorganic nitrides vapor phase epitaxy, has been used here to grow InN guantum dots capable of emitting in the near-infrared. Both In-polar and N-polar quantum dots have been grown and characterized, showing differences in morphology and emission by atomic force microscopy and photoluminescence.



Figure 6. XRD ω -2 θ scans around the (0002) reflection with InN relaxed peaks and GaN peaks for series C with GaN cap thicknesses of a) 0, b) 12, c) 18, and d) 23 nm.



400

350

300

250

200

150

50

PL intensity (a.u.

uncapped

12 nm

18 nm

23 nm